FORM PTO-1449 (REV.7-80)	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTY. DOCKET NO. 501306.01	APPLICATION NO. 10/683,977 ~~not yet assigned~~
INFORMATION DISCLOSURE STATEMENT *(Use several sheets if necessary)*		APPLICANT(S) Kie Ahn et al.	
		FILING DATE Concurrently herewith	GROUP ART UNIT 2822 ~~not yet assigned~~

U.S. PATENT DOCUMENTS

*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	AA						
	AB						
	AC						
	AD						

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO
	AE							
	AF							

OTHER PRIOR ART *(Including Author, Title, Date, Pertinent Pages, Etc.)*

MP	AG	Jeon, Sanghun, et al., "*Excellent Electrical Characteristics of Lanthanide Oxide and Lanthanide-doped Oxide for MOS Gate Dielectric Applications*," IEEE, 2001, pp. 01-471 to474
MP	AH	Kukli, Kaupo, et al., "*Influence of thickness and growth temperature one the properties of zirconium oxide films grown by atomic layer deposition on silicon*," Thin Solid Films 410, 2002, pp. 53-60.
MP	AI	Kukli, Kaupo, et al., " *Dielectric Properties of Zirconium Oxide Grown by Atomic Layer Deposition from Iodide Precursor*," Journal of The Electrochemical Society, Vol. 148, No. 12, 2001
MP	AJ	Kukli, Kaupo, et al., "*Properties of Ta_2O_5-Based Dielectric Nanolaminates Deposited by Atomic Layer Epitaxy*," Journal of The Electrochemical Society, Vol. 144, No. 1, 1997, pp. 300-306. January 1997
MP	AK	Kukli, Kaupo, et al., "*Atomic layer deposition of zirconium oxide from zirconium tetraiodide, water and hydrogen peroxide*," Journal of Crystal Growth, Vol. 231, 2001, pp. 262-272.
MP	AL	Sneh, Ofer, "*Thin film atomic layer deposition equipment for semiconductor processing*," Thin Solid Films 402, 2002, pp. 248-261.
MP	AM	Zhang, H., "*High permittivity thin film nanolaminates*," Journal of Applied Physics, Vol. 87, No. 4, 2000, pp. 1921-1924. [redacted] February 2000

EXAMINER	DATE CONSIDERED
	10/04

* EXAMINER: Initial if reference considered, whether or not criteria is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant(s).